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APPLICATION FOR A STANDARD PATENT

7880

Hoechst Aktiengesellschaft, of Rheingaustrasse 190, 6200 WIESBADEN, FEDERAL
REPUBLIC OF GERMANY

hereby applies for the grant of a standard patent for an invention entitled

Negative-working radiation-sensitive mixture with polymer having
1,2,3-thiadiazole groups, and recording material produced
therefrom

which is described in the accompanying complete specification.

Details of basic application(s):

Basic Application: Country:

Date:

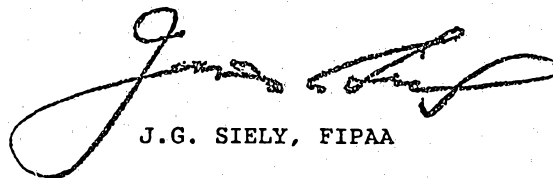
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DATED this TWELFTH day of OCTOBER 1989

Hoechst Aktiengesellschaft
By Its Patent Attorneys
ARTHUR S. CAVE & CO.


J.G. SIELY, FIPAA

TO:
The Commissioner of Patents
COMMONWEALTH OF AUSTRALIA

FEE: 220.00

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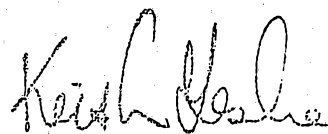
NOTICE OF ENTITLEMENT

HOECHST AKTIENGESELLSCHAFT, the applicant in respect of Application No.
42860/89 state the following:-

The Nominated Person is entitled to the grant of the patent because the Nominated Person derives title to the invention from the inventors Werner PRASS, Rudolph ZERTANI, Juergen LINGNAU, Norbert HANOLD, Herbert MEIER by assignment.

The Nominated Person is entitled to claim priority from the basic applications listed on the patent request form because the Nominated Person made the basic applications or has entitlement from the applications made in a Convention country in respect of the invention.

DATED this 16th day of September, 1991.



.....
a member of the firm of
ARTHUR S. CAVE & CO. for
and on behalf of the
applicant(s).

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- (54) Title
NEGATIVE-WORKING RADIATION-SENSITIVE MIXTURE WITH POLYMER HAVING 1,2,3-THIADIAZOLE GROUPS, AND RECORDING MATERIAL PRODUCED THEREFROM
- International Patent Classification(s)
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G03F 007/02
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- (56) Prior Art Documents
US 3457073

(57) 1,2,3-Thiadiazoles are known from the literature as photochemical crosslinking agents. US-A 3,457,073 describes their use in lithographic recording materials. In contrast to the polymers formed by polymerization of the compounds of the general formula I, the compounds described in this reference contain 1,2,3-thiadiazole groups bound to a polymer via carboxylate groups, i.e., the thiadiazole groups are incorporated in the macromolecule via a polymer-analogous reaction. However, this process has the disadvantage that complete reactions of the corresponding functional groups are hardly feasible and the starting substances which are not bound chemically cannot be separated off completely.

Compounds that react with ketene can contain one or more of -OH, -SH, -NHR, -NH₂, -NR₂, -COCl, -COOH, -CONH₂, -CONHR, -CSNH₂, -CSNHR, -NHNH₂, -CONHNH₂, -NH-N=CR₂, -N=C=O, $\begin{array}{c} \diagup \quad \diagdown \\ \text{C} \quad \text{C} \\ \diagdown \quad \diagup \\ \text{O} \end{array}$ and -CHO as functional groups.

CLAIM

1. A negative-working radiation-sensitive mixture comprising a binder and a polymer containing 1,2,3-thiadiazole groups, wherein the binder is a polyfunctional compound having functional groups that react with ketene and the polymer comprises a compound obtained by polymerization of a compound of the general formula I



in which R is a polymerizable group.

6. A negative-working radiation-sensitive mixture comprising a polymer containing 1,2,3-thiadiazole groups, wherein the polymer is obtained by polymerization of a compound of the general formula I



in which R is a polymerizable group, with a comonomer, and contains functional groups capable of reacting with ketenes.

8. A negative-working radiation-sensitive recording material consisting essentially of a substrate and a radiation-sensitive mixture as claimed in claim 1.

Our Ref: 295900

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FORM 10

COMPLETE SPECIFICATION

(ORIGINAL)

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Complete specification for the invention entitled

"Negative-working radiation-sensitive mixture with
polymer having 1,2,3-thiadiazole groups, and
recording material produced therefrom".

The following statement is a full description of this invention, including the
best method of performing it known to me:-

NEGATIVE-WORKING RADIATION-SENSITIVE
MIXTURE WITH POLYMER HAVING
1,2,3-THIADIAZOLE GROUPS, AND
RECORDING MATERIAL PRODUCED THEREFROM

5

Background of the Invention

The present invention relates to a negative-working, radiation-sensitive mixture containing a binder and a polymer having 1,2,3-thiadiazole groups.

10

Negative-working, radiation-sensitive mixtures have been extensively described in the literature. Despite various embodiments, the solubility of each of these radiation-sensitive mixtures in a suitable developer is diminished by a photochemically initiated reaction.

15

The abovementioned principle also occurs in a recording material containing unsaturated, polymerizable compounds in combination with a photoinitiator. The recording material is exposed image-wise by means of light or radiation in the absorption region of the photoinitiator and the

20

polymerization reaction which results is, if desired, accelerated by increasing the temperature.

The unexposed, i.e., unpolymerized areas of the recording material, are then removed by means of a suitable developer. EP-A 0,053,708 is representative of such a system.

In a different variation, the photoreaction leads to the formation of crosslinkable intermediates which are then crosslinked with suitable functional groups of other components present in the radiation-sensitive mixture, e.g., a binder. Radiation-sensitive mixtures of this type contain, for example, at least bifunctional azides as the radiation-sensitive component. Some of the many possible examples are described in DE-A 1,572,067, 1,572,068, 1,572,069 and 1,572,070.

There are also systems whose hydrophilicity changes upon exposure to light radiation. Classed with these systems are mixtures containing diazonium salts in combination with suitable binders. The exposure to light cleaves off nitrogen, which drastically reduces the alkali solubility of the radiation-sensitive mixture in the image-wise exposed areas as a result of subsequent reactions. These systems are described in EP-A 0,152,819 and 0,048,876.

While the first-mentioned photopolymerizable systems offer advantages with respect to sensitivity, since a reinforcing effect occurs through the radical-induced chain mechanism, the two last-mentioned systems offer advantages in the

resolution and quality of the structures which are reproduced.

Specifically, for producing structures by means of high-energy ionizing radiation (e.g.,
5 electron and X-rays), negative-working, light-sensitive mixtures based on polyacrylates and polychloromethylstyrenes are used. In these systems, a reinforcing effect is also present, although they are crosslinking systems, since the
10 quantum yield in these cases for the crosslinking reactions is considerably greater than one.

However, the negative-working, radiation-sensitive systems described are all very limited with respect to the radiation to be selected. Thus,
15 not only the radiation-sensitive mixtures containing components having azide groups but also those containing compounds having diazonium groups have absorption maxima in the near UV region (~365 nm), since the functional groups described are bound
20 directly to aromatic systems. However, radiation-sensitive mixtures of this type require a binder as an additional component. On the other hand, polyacrylates and polychloromethylstyrenes only have low sensitivity in the UV(II) region. They are
25 therefore extremely limited in their application range in this region.

Summary of the Invention

Accordingly, it is an object of the present invention to provide a radiation-sensitive mixture

suitable not only for lithography in the UV region,
but also for X-ray and electron beam lithography.

These and other objects according to the
invention are achieved by a negative-working
5 radiation-sensitive mixture comprising a binder and
a polymer, wherein the binder is a polyfunctional
compound having functional groups that react with
ketene and wherein the polymer is a compound
obtained by polymerization of a compound of the
10 general formula I



in which R is a polymerizable group. Compounds in
which R is vinyl, 2-propenyl or butadienyl are
particularly preferred.

15 Other objects, features and advantages of the
present invention will become apparent from the
following detailed description. It should be
understood, however, that the detailed description
and the specific examples, while indicating
20 preferred embodiments of the invention, are given by
way of illustration only, since various changes and
modifications within the spirit and scope of the
invention will become apparent to those skilled in
the art from this detailed description.

Detailed Description of the Preferred Embodiments

The compounds of the general formula I can be present as homopolymers. However, copolymers with other customary compounds containing unsaturated groups are also possible. These include styrenes, acrylic acids, methacrylic acids and derivatives thereof, in particular 2-hydroxyethyl methacrylate, maleic acid, itaconic acid and derivatives and esters thereof, vinyl phenols, vinyl acetates, vinyl alcohols and vinyl acetals. In particular, those comonomers containing free hydroxyl groups are preferred for polymerization with the compounds of the general formula I.

However, it is also possible to use those copolymers as binders which additionally contain monomers not having any of the functional groups described that react with ketene. In particular, the ratio of those components to those containing groups which react with ketenes, if there are two components, is about 0.1:1 to 1:1. However, the appropriate ratio for the particular combination also depends on the number of those functional groups which react with ketene and on the number of the various comonomers in the copolymer.

If, in the case of a copolymer containing monomers of the general formula I, the comonomer carries free hydroxyl groups, the binder containing groups that react with ketene can be omitted. If such a copolymer is present, the ratio of compounds of the general formula I to comonomers is about

0.1:1 to 1:0.1, in particular about 1:1. In this case, the amount of copolymer is about 46% by weight, while the amount of the compounds having functional groups capable of reacting with ketene is about 54% by weight, relative to the solids content of the mixture.

If the comonomer does not contain any free hydroxyl groups, the amount of the copolymer containing units of these comonomers is about 50% by weight, relative to the solids content of the radiation-sensitive mixture.

In this case, the amount of compounds having functional groups capable of reacting with ketene is about 10 to 40% by weight, in particular about 25% by weight, relative to the solids content of the radiation-sensitive mixture.

Compounds that react with ketene can contain one or more of -OH, -SH, -NHR, -NH₂, -NR₂, -COCl, -COOH, -CONH₂, -CONHR, -CSNH₂, -CSNHR, -NHNH₂, -CONHNH₂, -NH-N=CR₂, -N=C=O, $\begin{array}{c} \diagup \quad \diagdown \\ \text{C} \quad \text{C} \\ \diagdown \quad \diagup \\ \text{O} \end{array}$ and -CHO as functional groups.

Compounds containing -OH, -SH, -COCl, $\begin{array}{c} \text{O} \\ \diagup \quad \diagdown \\ \text{C} \quad \text{C} \\ \diagdown \quad \diagup \\ \text{O} \end{array}$, and NH₂ as functional groups are particularly preferred, and compounds having -OH groups and the binders from EP 0,152,819 are especially preferred. The functional groups mentioned can be present either in the main chain or in the side chain.

Examples of compounds containing the functional groups mentioned are phenolic resins of the novolak type, such as, for example, phenol/formaldehyde resins, cresol/formaldehyde resins,

their mixed condensation products and their mixtures, and phenol and cresol condensation products with other aldehydes. Further examples are glycidyl (meth)acrylates, polyvinyl phenols, polyvinyl alcohols, hydroxyalkyl methacrylates, i.e., synthetic compounds formed by polycondensation or polyaddition.

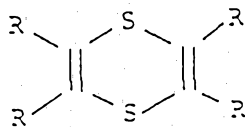
Natural polymers, such as, for example, cellulose, starch, dextrans and the like and their esters and ethers, provided they still carry free hydroxyl groups, are also used. Derivatives of cellulose and starch are, for example, hydroxyethylated or hydroxypropylated compounds.

In addition to the fact that the compound described above must have the functional groups as such, in order to be used as a component in the radiation-sensitive mixture according to the invention, it also has to be compatible with the remaining components in the mixture.

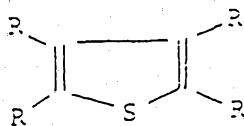
1,2,3-Thiadiazoles are known from the literature as photochemical crosslinking agents. US-A 3,457,073 describes their use in lithographic recording materials. In contrast to the polymers formed by polymerization of the compounds of the general formula I, the compounds described in this reference contain 1,2,3-thiadiazole groups bound to a polymer via carboxylate groups, i.e., the thiadiazole groups are incorporated in the macromolecule via a polymer-analogous reaction. However, this process has the disadvantage that complete reactions of the corresponding functional

Dimerization products, the basis for crosslinking:

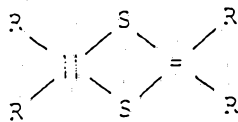
$$(1) + (4)$$



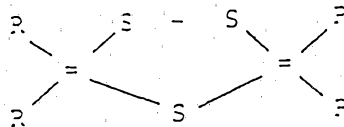
$$(1) + (2)$$



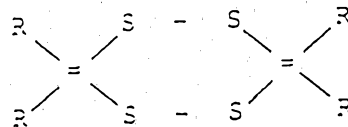
$$(1) + (5)$$



$$(3) + (5) + S$$



$$(5) + (5) + 2S$$



In other words, in principle these systems can be used for differentiation in lithographic layers. However, it was found that the sensitivities achievable are even worse than in systems described in US-A 3,457,073. It was therefore particularly surprising that, by use of this type of 1,2,3-thiadiazoles and compounds containing functional groups capable of reacting with ketene, an improved image differentiation could be achieved.

If desired, colorants, pigments, plasticizers, wetting agents and flow-improving agents as well as polyglycols, cellulose ethers, e.g., ethylcellulose, can be added to the radiation-sensitive mixture according to the invention to improve specific requirements such as flexibility, adhesion and gloss.

Preferably, the radiation-sensitive mixture according to the invention is dissolved in solvents such as ethylene glycol, glycol ethers (e.g., glycol monomethyl ether, glycol dimethyl ether, glycol monoethyl ether or propylene glycol monoalkyl ethers, in particular propylene glycol methyl ether), aliphatic esters (e.g., ethyl acetate, hydroxyethyl acetate, alkoxyethyl acetate, n-butyl acetate, propylene glycol monoalkyl ether acetate, in particular propylene glycol methyl ether acetate or amyl acetate), ethers (e.g., dioxane), ketones (e.g., methyl ethyl ketone, methyl isobutyl ketone, cyclopentanone and cyclohexanone), dimethylformamide, dimethylacetamide, hexamethylphosphoric

amide, N-methylpyrrolidone, butyrolactone, tetrahydrofuran and in mixtures thereof. Glycol ethers, aliphatic esters and ketones are particularly preferred.

5 The solutions formed by means of the components of the radiation-sensitive mixtures usually have a solids content of about 5 to 60% by weight, preferably up to about 50% by weight.

10 Furthermore, according to the invention, a radiation-sensitive recording material is provided which consists essentially of a substrate and the radiation-sensitive mixture applied thereto.

15 Suitable substrates are all materials of which capacitors, semiconductors, multi-layer printed circuits or integrated circuits can consist or from which they can be manufactured. Particularly suitable are surfaces consisting of pure, thermally oxidized and/or aluminum-coated silicon which may be doped or undoped, as well as all other
20 supports and substrates customary in semiconductor technology, such as silicon nitride, gallium arsenide and indium phosphide. Further suitable substrates are those known from liquid crystal display manufacture, such as glass or indium/tin
25 oxide. Metal plates and sheets (for example, made of aluminum, copper, zinc), bimetal and trimetal sheets, as well as electrically non-conducting sheets metallized by vapor deposition, for example, aluminum-coated SiO_2 materials and paper, are also
30 suitable. These substrates can be subjected to a pretreatment by heating, roughened on the surface,

etched or treated with chemicals to improve desirable properties, e.g., hydrophilicity.

5 In a particular embodiment, the radiation-sensitive mixture can contain, in the resist or between the resist and the support or substrate, an adhesion promoter for better adhesion. In the case of silicon or silicon dioxide substrates, suitable adhesion promoters are of the aminosilane type, e.g., 3-aminopropyltriethoxysilane
10 or hexamethyldisilazane.

The recording material according to the invention is subjected to image-wise irradiation by means of high-energy radiation sources; electron or X-rays are preferred. If sufficiently transparent
15 binders are used, image-wise irradiation by means of short-wave UV radiation (deep UV) is also possible.

The layer thickness varies depending on the particular use. It is about 0.1 to 1000, in particular about 1 to 10, μm .

20 The radiation-sensitive mixture can be applied to the substrate by spraying, flow-coating, rolling, spin-coating and dip-coating. The solvent is then removed by evaporation so that the radiation-sensitive layer remains on the surface of
25 the substrate. The removal of the solvent can, if necessary, be promoted by heating the layer to temperatures of up to about 150° C. However, it is also possible to apply the mixture in the abovementioned manner first to an intermediate
30 substrate from which it is transferred to the final substrate under pressure and elevated temperature.

The intermediate substrates that can be used are in principle all materials mentioned above as suitable substrates, as long as they are flexible.

5 After application to the intended substrate, the layer is subjected to image-wise radiation. Preferably, high-energy radiation such as X-ray or electronic radiation is used; high energy synchrotron radiation having dosage values of about 20 to 200 mJ/cm² or the radiation of an electron beam
10 writer is particularly preferred. The actual differentiation reaction (crosslinking) can in individual cases take place at room temperature. However, as a rule, additional heating (post-exposure bake) lasting from about 1 to 30
15 minutes, and preferably taking place at temperatures of about 90 to 150° C, is favorable. In the radiation-sensitive layer, an image pattern is then exposed by development by treating the layer with a developer solution which dissolves or removes the
20 non-exposed areas of the material.

The developers used are solutions of alkaline reagents such as silicates, metasilicates, hydroxides, hydrogen or dihydrogen phosphates, carbonates or bicarbonates, in particular, of alkali
25 metal or ammonium ions, but also of ammonia or organic ammonium bases and the like. The proportion of these substances in the developer solution is, in general, about 0.1 to 15% by weight, preferably about 0.5 to 5% by weight, relative to the weight
30 of the developer solution.

The preparation of the copolymers contained in the radiation-sensitive mixture according to the invention will be illustrated by means of the examples which follow.

5 Example 1

 a) Copolymerization of 4-vinyl-1,2,3-thiadiazole with 2-hydroxyethyl methacrylate.

 2.00 g (17.8 mmol) of 4-vinyl-1,2,3-thiadiazole and 2.32 g (17.8 mmol) of 2-hydroxyethyl methacrylate are dissolved together with 59 mg of azobisisobutyronitrile in 20 ml of dried tetrahydrofuran. A dry nitrogen stream is passed through the solution at 20° C for one hour. The mixture is heated to 65° C and refluxed for 6 hours.
10
15 After the reaction is completed, the polymer obtained is precipitated with 400 ml of hexane, filtered with suction and dried at room temperature in vacuo. This gives 0.6 g of a slightly yellow, glass-like solid soluble in dimethylformamide, N-methylpyrrolidone and THF.
20

 The determination of the molecular weight by gel permeation chromatography gives an M_v of 8000 and an M_n of 3300 (polystyrene calibration). Elemental analysis (50.6% C, 6.4% H, 10.0% N and 11.6% S) shows a copolymer composition of one part of 4-vinyl-1,2,3-thiadiazole to 1.4 parts of 2-hydroxyethyl methacrylate.
25

 b) Structuring of the copolymer by means of electron beams.

5 A silicon wafer (not oxidized) is cleaned by means of ethanol and coated with a 3% solution of the copolymer described in a) in tetrahydrofuran by means of a spin coater (5 seconds at 1000 revolutions per minute). A layer thickness of 0.4 μm is obtained.

10 A striped pattern is written into the layer by means of a scanning electron microscope containing a pattern generator at various energy doses in the range from 5 to 200 $\mu\text{C}/\text{cm}^2$. The patterns are developed by immersion into tetrahydrofuran for 10 seconds. The result is that even at a dosage of 20 $\mu\text{C}/\text{m}^2$ the structures are completely resistant to the developer and have good
15 edge sharpness (better than 0.1 μm).

Example 2 (Comparative Example)

a) Polymerization of 4-vinyl-1,2,3-thiadiazole-5-carboxylic acid.

20 The procedure of the process is as in Example 1a).

b) Structuring of poly(4-vinyl-1,2,3-thiadiazole)-5-carboxylic acid.

25 A silicon wafer (not oxidized) is cleaned analogously to Example 1b) and coated with a 0.4 μm thick layer of poly(4-vinyl-1,2,3-thiadiazole)-5-carboxylic acid.

30 A striped pattern is written into the layer by means of a scanning electron microscope containing a pattern generator at various energy doses in the range from 10 to 350 $\mu\text{C}/\text{cm}^2$. The

patterns are developed by immersion into tetrahydrofuran for 30 seconds. Only at and above a dosage of $150 \mu\text{C}/\text{cm}^2$ do parts of the structures not dissolve in the developer; however, the differentiation of the patterns is insufficient. A longer development time (> 1 minute) ultimately dissolves the irradiation layer completely, so that no image whatsoever is obtained.

Example 3

10 Structuring of poly(4-vinyl-1,2,3-thiadiazole) in a mixture with a copolymer consisting of methyl methacrylate and glycidyl methacrylate (1:1).

15 A silicon wafer (not oxidized) is cleaned analogously to Example 1b) and coated with a $0.4 \mu\text{m}$ thick layer consisting of 50% by weight of poly(4-vinyl-1,2,3-thiadiazole) and 50% by weight of the copolymer consisting of methyl methacrylate and glycidyl methacrylate (1:1).

20 A striped pattern is written into the layer by means of a scanning electron microscope containing a pattern generator and various energy doses in the range from 5 to $200 \mu\text{C}/\text{cm}^2$. The patterns are developed by immersion into acetone for
25 60 seconds. Only at and above a dosage of $5 \mu\text{C}/\text{cm}^2$ is it possible to obtain a completely and well-resolved structure having a high edge sharpness.

Example 4

Structuring of poly(4-vinyl-1,2,3-thiadiazole) in a mixture with an m-cresol/formaldehyde novolak.

- 5 A silicon wafer (not oxidized) is cleaned analogously to Example 1b) and coated with a 0.4 μm thick layer consisting of 50% by weight of poly(4-vinyl-1,2,3-thiadiazole) and 50% by weight of an m-cresol/formaldehyde novolak of a softening
10 range of 105 to 120° C.

- A striped pattern was written into the layer by means of a scanning electron microscope containing a pattern generator at various energy doses in the range from 5 to 200 $\mu\text{C}/\text{cm}^2$. The
15 patterns are developed by immersion into acetone for 60 seconds. At a dosage of as low as 10 $\mu\text{C}/\text{cm}^2$, a completely and well-resolved structure having a high edge sharpness is obtained.

The Claims defining the invention are as follows:

1. A negative-working radiation-sensitive mixture comprising a binder and a polymer containing 1,2,3-thiadiazole groups, wherein the binder is a polyfunctional compound having functional groups that react with ketene and the polymer comprises a compound obtained by polymerization of a compound of the general formula I



in which R is a polymerizable group.

2. A radiation-sensitive mixture as claimed in claim 1, wherein R is selected from the group consisting of vinyl, 2-propenyl and butadienyl.

3. A radiation-sensitive mixture as claimed in claim 1, wherein the compound that reacts with ketene is a polyfunctional alcohol.

4. A radiation-sensitive mixture as claimed in claim 1, wherein the polymer is a copolymer.

5. A radiation-sensitive mixture as claimed in claim 4, wherein the copolymer comprises a comonomer containing functional groups capable of reacting with ketene.

6. A negative-working radiation-sensitive mixture comprising a polymer containing 1,2,3-thiadiazole groups, wherein the polymer is obtained by polymerization of a compound of the general formula I



in which R is a polymerizable group, with a comonomer, and contains functional groups capable of reacting with ketenes.

7. A radiation-sensitive mixture as claimed in claim 6, wherein the comonomer is a monomer containing alcoholic hydroxyl groups.

8. A negative-working radiation-sensitive recording material consisting essentially of a substrate and a radiation-sensitive mixture as claimed in claim 1.

9. A negative-working radiation-sensitive mixture substantially as herein described with reference to any one of Examples 1;3 or 4.

DATED the 12th day of October, 1989

HOECHST AKTIENGESELLSCHAFT
By Its Patent Attorneys
ARTHUR S. CAVE & CO.